

ABSTRACT

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“JUDICIAL REVIEW OF LEGAL PROTECTION OF PATTERN AND SKETCH OF FASHION DESIGNERS”

(xi + 123 pages + 15 Pictures)

Nowadays, Industrial Fashion has been grown so fast and become as one of country financial revenue in one time. Indonesia have so many Fashion Designers has been well-known in international community. But, there are still some weakness in legal protection of Industrial Fashion here. Many Fashion Designers do not understand with the legal protection that attached to their creations. Pattern may be protected by Copyright, but the other side can be protected by Industrial Design also. The overlapping between Copyright and Industrial Design makes some obscurity of legal to protect the pattern of Fashion Designers themselves. This thesis apply kinds of research methodology as follows, the Statute Approach based on Copyrights Law and Industrial Design Law, and The Conceptual Approach. The analysis is meant to see the overlapping between Copyrights and Industrial Design that may caused in practically there are so many well-known Fashion Designers pattern that sold freely in different quality but there are no punishments. So, The conclusion is the protection based on the original purpose of Fashion Designers. If the creations is for own collections that it will be protected by Copyright, but if the creations made for commercial things, it will protected by Industrial Design Law.

References : 36 (2002-2015)